

10/588,163

Please replace the paragraph beginning on page 7, line ³~~2~~, with the following rewritten paragraph:

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According to a second aspect of the present invention, there is provided an exposure apparatus (~~EX~~) which exposes a substrate (~~P~~) by radiating an exposure light beam (~~EL~~) onto the substrate (~~P~~) through a liquid (~~LQ~~); the exposure apparatus comprising a mover (~~PST~~) which holds the substrate; a driving unit (~~PSTD~~) which moves the mover (~~PST~~); and a control unit (~~CONT~~) which controls the driving unit (~~PSTD~~) and includes first control information to move the mover (~~PST~~) in the presence of the liquid (~~LQ~~) supplied onto the mover (~~PST~~), and second control information to move the mover (~~PST~~) in the absence of the liquid (~~LQ~~) supplied onto the mover (~~PST~~).

Please replace the paragraph beginning on page 7, line ~~23~~ with the following rewritten paragraph:

According to a third aspect of the present invention, there is provided a position control method for controlling a position of a mover (~~PST~~) by using a reflecting surface (~~MX~~, ~~MY~~) formed on the mover (~~PST~~) which holds a substrate (~~P~~) in an exposure apparatus (~~EX~~) for exposing the substrate (~~P~~) by radiating an exposure light beam (~~EL~~) onto the substrate (~~P~~) through a liquid (~~LQ~~); the position control method comprising measuring error information about an error of the reflecting surface (~~MX~~, ~~MY~~) in the presence of the liquid (~~LQ~~) supplied onto the mover (~~PST~~); and controlling the position of the mover (~~PST~~) on the basis of the error information.

Please replace the paragraph beginning on page 8, line ¹⁹~~23~~, with the following rewritten paragraph:

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